Analysis of Structural Transformations in High Fluence Nitrogen Ion Implanted Aluminium

Amorphization of Fe/Zr Multilayers by Ar-Ion-Beam-Mixing

Amorphization of Zr/Ni Bilayers by Ion-Beam-Mixing

Atomic Transport in Irradiated Solids

Ion Irradiated Amorphous Silicon: A Model Approach to Dynamics of Defect Creation and Annihilation

Temperature Dependence of Ion Beam Mixing of InGaAs Marker Layers in GaAs


Electron Irradiation Induced Crystallization of Amorphous Al[subscript 2]O[subscript 3] Films on Silicon Substrates

Strain Relief by Ion Beam Mixing, Molecular Dynamics Simulations Applied to Metallic Hetero-Structures

Silicide Formation in Ti-Si and Co-Si Reactions

Activation Energy for the C49-To-C54 Phase Transition of Polycrystalline TiSi, Films With Under 30nm Thickness

Time Resolved X-Ray Diffraction Study of the Transformation Kinetics of TiSi[subscript 2]-C49 in Amorphous Si/Ti Multilayers

Phase Transition and Formation of TiSi[subscript 2] Codeposited on Atomically Clean Si(111)

Phase Transformation Kinetics of TiSi[subscript 2]

Equilibrium Shape of CoSi[subscript 2] in Silicon

Evolution of Cubic FeSi[subscript 2] in Si Upon Thermal Annealing

Prediction of Silicide Formation Sequence from the Principle of the Largest Free Energy Degradation Rate

Phase Transformation of Co Silicidation in the Co/Ti- and Ti/Co-Si(100) Systems

Reaction Rate Kinetics and Film Textures of Palladium Silicide Formed on Hydrogenated Amorphous Silicon

Contact Reactions at Cu/a-Ge Thin Film Couples

Simultaneous Occurrence of Multiphases in the Interfacial Reactions of Ultrahigh Vacuum Deposited Ti, Hf and Cr Thin Films on (111)Si

Phase Transformation of Mo and W Over Co or Its Alloy in Contact with Si

Direct Deposition Reactions Between Nickel and Silicon Substrates

Hydrogen Evolution and Interface Reaction of Cu Thin Film on a-Si:H

Variations of Fractal Dimension During the Phase Transformation to the Silicide Nucleation in Thin Film Systems

At Atomistic Study of Surface Vacancy Diffusion

Sputter Deposition and Thermally Induced Phase Transformation of Non-BCC Chromium Thin Films

The Influence of Deposition Pressure on the Incorporation of Target and Ambient Oxygen into Laser Ablated Material

Electron Microscopy Study of Cubic Boron Nitride Thin Films Grown by Ion-Assisted Pulsed Laser Deposition

Microstructure of Si Films Deposited on Si(100) Surfaces by Remote Plasma-Enhanced Chemical-Vapor Deposition, RPECVD: Dependence on Process Pressure and Substrate Temperature